



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#8190.00ndtA  
8/18/02  
Q.McKinney

Applicant: Michael Weber-Grabau et al. PATENT APPLICATION  
Serial No.: 09/927,102 Group Art Unit:  
Filed: August 10, 2001 Examiner:  
For: OPTICAL CRITICAL DIMENSION METROLOGY  
SYSTEM INTEGRATED INTO SEMICONDUCTOR  
WAFER PROCESS TOOL

Preliminary Amendment

Hon. Assistant Commissioner  
for Patents  
Washington, D.C. 20231

Sir:

Prior to a first Office action, please amend the above-identified patent application as follows:

In the specification:

On page 1, after the title of the application and before the subheading "TECHNICAL FIELD", please insert - -

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A<sup>1</sup> CROSS-REFERENCE TO RELATED APPLICATION

This application claims priority under 35 U.S.C. 119(e) from prior U.S. provisional application no. 60/224,571, filed August 11, 2000. - -

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